

# The Impact of Market Regulation and Distance to Frontier on Innovation and Productivity

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# Motivation

- Lisbon strategy: make the EU the most competitive knowledge-based economy.
- Rationale: more product market competition (less regulation) should bolster innovation and thus productivity and (ultimately) economic growth.
- However, economic research (both theoretical and empirical) suggests that there remain ambiguities in the relationship between competition and innovation.
- The present research re-examines this relationship empirically, using an original application of the "CDM" econometric framework linking R&D, innovation and productivity.

# Summary of the presentation

- Review of the (theoretical and empirical) literature on competition and innovation
- Econometric modelling and data: from the knowledge production function to the CDM framework
- Preliminary results
- Conclusion

# Competition and innovation

- Post-Schumpeterian economics generally expect an inverted-U relationship between competition and innovation.
- This inverted-U relationship is supported in many empirical studies (e.g., Scherer, 1965, *AER*; Acs and Audretsch, 1987, *Rev. Econ. Statist.*; Cohen and Levin, 1989; Baldwin et al. 2002, Aghion et al. 2005).
- However, Boone (2001) explains that a non-monotone relation between competition and innovation does not necessarily imply, for a particular market, that an increase in the former improves firms' incentives to innovate (Boone, 2001, *IJO*, p. 16).

# The inverted-U relationship

- Aghion et al. (2005), *QJE*, model the aforementioned inverted-U relationship as resulting from a positive "escape competition" effect and a negative "Schumpeterian" effect
- They consider an economy w/ levelled ("neck-and-neck") and unlevelled industries
- Under the (critical) assumption of automatic catch-up by the follower in unlevelled industries, they show that the "escape competition" effect dominates in levelled industries whereas the "Schumpeterian" effect dominates in unlevelled ones
- In other words, in this framework, innovation tends to increase w/ competition in levelled industries, and to decrease w/ competition in unlevelled ones.

# Distance to frontier

- Aghion et al. (2005)'s model predicts that the "escape competition" effect tends to be stronger in industries that are closer to the technological frontier.
- In other words, competition should increase innovation in industries that are closer to the technological frontier
- However, using OECD industry-level data, Amable et al. (2010) find that product market regulation tend to increase innovation in industries that are closer to the technological frontier
- They show that this empirical result, which contradicts the above prediction, can be theoretically grounded if one includes interactions between leader and follower's innovation in Aghion et al. (2005)'s model.

# What we do

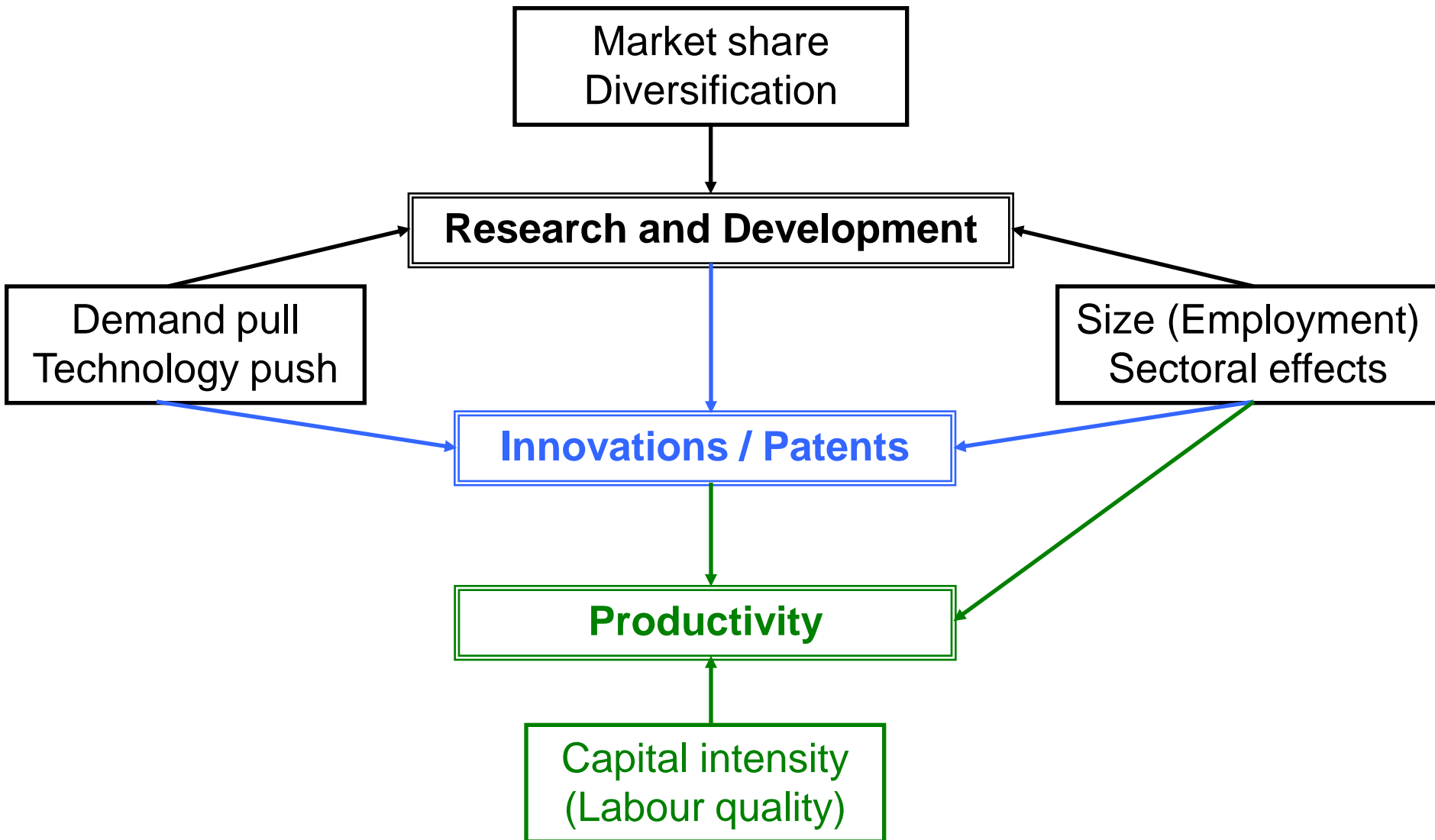
- We check whether Amable et al. (2010)'s conclusions, derived from the estimation of a knowledge production function, still hold in a broader framework linking R&D, innovation and productivity.
- The so-called "CDM" model (from Crépon, Duguet, Mairesse, 1998, *Econ. Innov. New Tech*) provides such a framework, primarily for firm-level data.
- We adapt the specification of this model to a panel of industries similar to the one used in Amable et al. (2010), to re-examine how product market regulation and distance to frontier influence the R&D – Innovation – Productivity relationship.

# What we find

- A positive effect of product market regulation on R&D expenditures in industries that are closer to the world technological frontier
- A positive effect of R&D expenditures on innovation (measured by patenting intensity) in the leading industries
- A positive (negative/insignificant) effect of patenting on productivity in the leading (laggard) industries.



# The original CDM model (firm-level)



# Applications of the CDM model

Reference	Data	Specification	Estimation
Crépon, Duguet, Mairesse, 1998, <i>Econ. Innov. New Tech.</i>	Cross section (CIS)	Type II Tobit + linear/count models	LIML + ALS
Griffith, Huergo, Peters, Mairesse, 2006, <i>Oxford Rev. Econ. Pol.</i>	Cross section (CIS)	Type II Tobit + Probit + linear model	LIML
Benavente, 2006, <i>Econ. Innov. New Tech.</i>	Cross section (CIS-type)	Type II Tobit + ordered Probit + linear model	LIML + ALS
Chudnovsky, Lopez, Pupato, 2006, <i>Res. Pol.</i>	Panel data	Logit w/ FE + multinomial Logit + linear models w/ FE	LIML
OECD, 2009	Cross section (CIS-typ)	Type II Tobit + linear models	LIML
Raymond <i>et al.</i> , 2009, CIRANO WP	Panel data	RE multivariate Tobits	FIML

# Our application

- So far, the "CDM" model has been estimated on microeconomic data only.
- However, if the "knowledge production function" can be applied to various economic units (Mairesse and Mohnen, *AER*, 2002), the same must be true of the "CDM" model.
- Applying the CDM model to a panel of industries:
  - requires one to rethink the choice of variables
  - limits missing observations problems
  - allows one to specify the model using three linear equations
  - allows one to use FE estimation

# Data sources

- EU KLEMS data on output, input and productivity measures (<http://www.euklems.net>; O'Mahony and Timmer, 2009).
- Data on patenting from EUROSTAT
- Regulation proxies computed by the OCDE
- R&D stock provided by EUKLEMS-Linked data (O'Mahony et al., 2008)
- We keep a balanced panel of 13 industries observed across 13 countries (i.e. 169 industry-country) over 24 years (1980-2003)

# The EUKLEMS industry panel

- Unit of analysis: industry-country  $i$ , observed at time  $t$ :

Industry	
Code	Name
15-16	Food, Beverages and Tobacco
17-19	Textile, Leather and Footwear
20	Wood, Wood and Cork Products
21-22	Pulp and Paper, Printing and Publishing
23	Coke, Refined Petroleum and Nuclear Fuel
24	Chemicals and Chemical Products
25	Rubber and Plastic
26	Other Non-Metallic Minerals
27-28	Basic Metal and Fabricated Metal
29	Machinery
30-33	Electrical and Optical Equipment
34-35	Transport Equipment
36-37	Other Manufacturing, Recycling

Country
Australia
Denmark
Finland
France
Germany
Ireland
Italy
Japan
Netherlands
Spain
Sweden
United Kingdom
USA

# Key variables

- **R&D intensity:** R&D stock on total (employees) hours worked
- **Patenting intensity:** # of patents on total hours worked
- **TFP:** computed based on value-added
  
- **MHS:** # of Medium/High Skill labour hours worked in the industry
- **ext:** patenting externalities (patenting intensity in other industries-countries)
- **regimp:** importance of product market regulation (OECD Index)

# Econometric modelling

- According to Aghion et al. (2005), what matters is the difference between pre- and post-innovation rents: "*competition may increase the incremental profits from innovating, and thereby encourage R&D investments aimed at "escaping competition"*".
- To take this into account, we specify an econometric model in which product market regulation impacts R&D but not the output of the innovation process.
- We let R&D affect the output of the innovation process (measured by patenting intensity), which in turn may affect TFP

# Specification and estimation

- Our model is specified as a three equation system:

$$\begin{cases} \ln RD_{it} = \alpha_0 + \alpha_1 \ln ext_{it} + \alpha_2 \ln MHS_{it} + \alpha_3 \ln regimp_{it} + v_{1t} + u_{1i} + \omega_{1it} \\ \ln patents_{it} = \beta_0 + \beta_1 \ln RD_{it} + \beta_2 \ln ext_{it} + \beta_3 \ln MHS_{it} + v_{2t} + u_{2i} + \omega_{2it} \\ \Delta \ln TFP_{it,t-1} = \gamma_0 + \gamma_1 \ln patents_{it-1} + \gamma_2 \ln patents_{it-2} + \gamma_3 \ln patents_{it-3} + v_{3t} + u_{3i} + \omega_{3it} \end{cases}$$

with  $v_{kt}$  = year FE,  $u_{ki}$  = individual FE,  $\omega_{kit}$  = error term ( $k = 1,2,3$ ).

Note that  $RD$  = R&D intensity and  $patents$  = patenting intensity.

- The first two equations are estimated as an IV system with FE
- The third equation is estimated as an additional FE regression using the predicted value of patenting intensity as a covariate (standard errors are bootstrapped).



# Measuring distance to frontier

- We estimate the above system separately for industries that are closer to the world technology frontier (hereafter "leaders") and for those that are further away from the frontier (hereafter "followers")
- We define "leaders" as industries where the TFP is above a certain quantile of the global TFP distribution (Q50, Q60, Q75)
- We define "followers" as industries where the TFP is below a certain quantile of the global TFP distribution (Q50, Q40, Q25)
- In what follows, we take as our benchmark the estimates obtained with the definition of leaders/followers based on Q50.

# Benchmark results: leaders

	log R&D intensity	log patenting intensity	TFP growth
log ext	0.351 *** (0.071)	0.482 *** (0.08)	—
log MHS	0.349 *** (0.06)	0.994 *** (0.063)	—
log regimp	0.802 *** (0.087)		—
log RDint	—	0.634 *** (0.103)	—
log patents <sub>t-1</sub> (predicted)	—	—	-0.017 (0.017)
log patents <sub>t-2</sub> (predicted)			-0.027 (0.026)
log patents <sub>t-3</sub> (predicted)			0.050 ** (0.024)
Constant	3.066 *** (0.312)	-6.663 *** (0.34)	0.037 *** (0.013)
Year dummies	Yes	Yes	Yes

# Benchmark results: followers

	log R&D intensity	log patenting intensity	TFP growth
log ext	0.287*** (0.101)	0.887*** (0.115)	—
log MHS	0.881*** (0.072)	1.201*** (0.244)	—
log regimp	-0.370*** (0.115)		—
log RDint	—	-0.003 (0.263)	—
log patents <sub>t1</sub> (predicted)	—		0.063** (0.025)
log patents <sub>t2</sub> (predicted)			0.023 (0.041)
log patents <sub>t3</sub> (predicted)			-0.071* (0.039)
Constant	-1.348*** (0.416)	-5.326*** (0.343)	-0.070** (0.036)
Year dummies	Yes	Yes	Yes

# Closer to the frontier...

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	>Q50	>Q60	>Q75
Effect of log regulation on log R&D intensity	0.802*** (0.087)	0.804*** (0.091)	1.011*** (0.118)
Effect of log R&D int on log patenting	0.634*** (0.103)	0.716*** (0.113)	0.866*** (0.117)
Effect of patenting at $t-1$ on TFP growth	-0.017 (0.017)	0.024 (0.023)	0.008 (0.01)
Effect of patenting at $t-2$ on TFP growth	-0.027 (0.026)	-0.057 (0.046)	-0.005 (0.013)
Effect of patenting at $t-3$ on TFP growth	0.050** (0.024)	0.045 (0.035)	0.007 (0.009)

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# Further away from the frontier...

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	<Q50	<Q40	<Q25
Effect of log regulation on log R&D intensity	-0.370*** (0.115)	-0.374*** (0.132)	-0.084 (0.186)
Effect of log R&D int on log patenting	-0.003 (0.263)	-0.458 (0.375)	-2.38 (6.064)
Effect of patenting at $t-1$ on TFP growth	0.063** (0.025)	0.172*** (0.061)	0.012 (0.018)
Effect of patenting at $t-2$ on TFP growth	0.023 (0.041)	-0.011 (0.062)	-0.033 (0.021)
Effect of patenting at $t-3$ on TFP growth	-0.071* (0.039)	-0.095** (0.045)	0.033** (0.014)

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# Main findings

- Using a panel of industries, we examined the impacts of:
  - product market regulation on R&D
  - R&D on innovation
  - innovation on TFP growth
- A separate analysis for industries that are closer to / further from the world technology frontier reveals that:
  - Product market regulation has a positive (negative) impact on R&D expenditures closer to (further away from) the frontier
  - In "leader" industries, innovation intensity increases with R&D intensity, and feeds the growth of TFP

# Conclusions

- We find the expected virtuous circle between R&D, innovation and economic growth
- However, our results suggest that the way distance to frontier affects the relationship between competition and R&D expenditures remains ambiguous
- In particular, our preliminary results show a positive effect of product market regulation on R&D closer to the technology frontier

# Further research and implications

- We need to conduct extended robustness checks of our results (e.g., GMM, simultaneous estimation)
- Provided that they are robust, they suggest that deregulation should not be expected to systematically improve the R&D effort
- This would be in line with some industry-specific studies (e.g. Jasmab and Pollitt, *Res. Pol.*, 2008)
- Therefore, deregulation as a policy instrument should be considered on a case-by-case basis rather than systematically.